

ABSTRACT OF THE DISCLOSURE

An exposure apparatus that exposes a pattern of a mask onto a substrate is provided with a projection system that projects the pattern onto a substrate, a holder that holds the projection system, a detector that detects information concerning displacement (e.g., oscillation) of the projection system, an actuator that is arranged in the holder, and a driver that drives the actuator corresponding to the detection results of the detector. Therefore, when, for example, displacement caused by vibration is generated in the holder of the projection system, the detector detects information concerning this displacement and outputs this information to the driver. By driving the actuator with the driver, the actuator controls displacement generated in the holder by canceling the detected displacement. This improves positioning accuracy and pattern projection accuracy of the exposure apparatus by controlling displacement caused by oscillation generated in the projection system.